

*“Phase formation in intermixed NiGe thin films : influence of Ge content and low temperature nucleation of hexagonal nickel germanides”*. De Schutter B, Devulder W, Schrauwen A, van Stiphout K, Perkisas T, Bals S, Vantomme A, Detavernier C, Microelectronic engineering **120**, 168 (2014). <http://doi.org/10.1016/j.mee.2013.09.004>